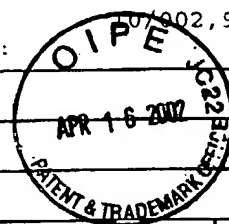


FORM PTO-1449	Atty. Docket Number: H60-104 US	Serial Number: 10/202,996
LIST OF PRIOR ART CITED BY APPLICANT	Applicant: J. Ramm	
	Filing Date: 10/25/01	Group:



U.S. PATENT DOCUMENTS

EI*		Document Number	Date	Name	Class	Sub-class	Filing Date
FH	AA	4 0 5 8 4 3 0	11/15/77	Suntola et al.	156	611	11/25/75
↑	AB	4 3 8 9 9 7 3	06/28/83	Suntola et al.	118	275	12/11/81
	AC	4 4 1 3 0 2 2	11/01/83	Suntola et al.	427	255.2	06/21/79
	AD	5 0 7 1 6 7 0	12/10/91	Kelly	427	38	06/11/90
	AE	5 9 1 6 3 6 5	06/29/99	Sherman	117	92	08/16/96
↓	AF	5 9 7 2 4 3 0	10/26/99	DiMeo, Jr. et al.	427	255.3	11/26/97
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	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		Document Number	Date	Country	Class	Sub-class	Translated	
							Y	N
	AL							
	AM							
	AN							
	AO							
	AP							

Other Prior Art (incl. Author, Title, Date, Pertinent Pages, etc.)

FH	AR	Hiramatsu, K, et al., "Formation of TiN films with low CI concentration by pulsed plasma chemical vapor deposition", <u>J. Vac. Sci. Technol.</u> A 14(3) May/Jun 1996, 1037-1040.
FH	AS	Rossnagel, S.M., "Plasma-enhanced atomic layer deposition of Ta and Ti for interconnect diffusion barriers", <u>J. Vac. Sci. Technol.</u> B 18(4), Jul/Aug 2000, 2016-2020.
FH	AT	Swiss Search Report, dated July 27, 2001.

Examiner: *F. H. Hirsch*

Date Considered: 1/14/04

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with 1 Draw line through citation if not in conformance and not considered. Include copy of this 1 next communication to applicant.